

U.S. Department of Commerce, Patent and Trademark				Atty. Docket No.		Application No.	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				TNCR.188US0 (formerly M-10699 US)		09/671,715	
				Applicant(s)		Conf. No.	
(Use several sheets if necessary)				Anatoly FABRIKANT et al.		6087	
(Form PTO-1449)				Filing Date		Art Group	
				September 27, 2000		2877	

U.S. Patent Documents							
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
SL	A1	6,768,967 B2	07/27/2004	JOHNSON et al.	702	179	
SL	A2	6,097,488	08/01/2000	GREK et al.	356	364	
SL	A3	5,739,909	04/14/1998	BLAYO et al.	356	369	
SL	A4	5,751,427	05/12/1998	DE GROOT	356	358	
SL	A5	6,268,916 B1	07/31/2001	LEE et al.	356	364	
SL	A6	5,900,939	05/04/1999	ASPNES et al.	356	369	
SL	A7	5,978,074	11/02/1999	OPSAL et al.	356	72	

U.S. Published Patent Application Documents							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	

Foreign Patent Documents								
							Translation	
	Document	Date	Country	Class	Subclass	Yes	No	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
SL	D1	US Provisional Appln. No. 60/224,451, filed 08/10/2000, to STANKE et al., cited in USP 6,768,967, 28 pgs.
SL	D2	LI, "Formulation and Comparison of Two Recursive Matrix Algorithms for Modeling Layered Diffraction Gratings", J. Opt. Soc. Am. A/Vol. 13, No. 5 / May 1996, pp. 1024-1035.
SL	D3	International Search Report from corresponding PCT Appln. PCT/US01/30063, dated 12/21/01, 4 pages.
SL	D4	Written Opinion from corresponding PCT Appln. PCT/US01/30063, dated 9/18/2002, 5 pages.
SL	D5	International Preliminary Examination Report from corresponding PCT Appln. PCT/US01/30063, dated 1/16/2003, 6 pages.
SL	D6	Patent Search conducted on August 1, 2000 (53 pages).

Examiner	Date Considered
SL	12/26/2005

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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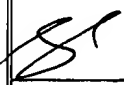
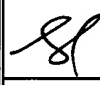

  

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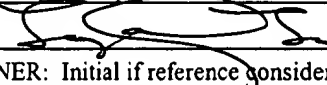
  

Foreign Patent Documents								
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	Document	Date	Country	Class	Subclass	Yes	No	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
	D7	BLAYO et al., "Ultraviolet-Visible Ellipsometry for Process Control During the Etching of Submicrometer Features" J. Opt. Soc. Am. A., vol. 12, No. 3, Mar. 1995, pp. 591-599.
	D8	SCHRAMM et al., "Algorithm Implementation and Techniques for Providing More Reliable Overlay Measurements and Better Tracking of the Shallow Trench Isolation (STI) Process", SPIE: Conference on Metrology, Inspection, and Process Control of Microlithography XIII., Mar. 1999, pp. 116-122.
	D9	MOHARAM, "Coupled-Wave Analysis of Two-Dimensional Dielectric Gratings", SPIE: Vol. 883; Holographic Optics: Design and Applications (1988), pp. 8-11.
	D10	International Application Pub. No. WO02/50501 A1, published with International Search Report on June 27, 2002.
	D11	MOHARAM et al., "Formulation for Stable and Efficient Implementation of the Rigorous Coupled-Wave Analysis of Binary Gratings", J. Opt. Soc. Am. A./Vol. 12, No. 5, May 1995, pp. 1068-1076.

Examiner 	Date Considered <u>12/26/05</u>
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